



ISO 5 Cleanroom facilities

State-of-the-Art Cleanroom Facilities & Services

JD7's cleanroom facilities are specifically designed to meet the highest technical standards and to adapt to the evolving needs of high-precision industries operating in ultra-clean environments.

The infrastructure is tailored to support both advanced research and development as well as full-scale industrial operations, offering maximum flexibility—particularly for applications in microelectronics, microfabrication, and microsystems engineering. Each cleanroom unit is fully managed and maintained by the building owner, allowing tenants to focus entirely on their core processes and value-added activities.

Cleanroom surfaces available for rent

JD7 offers modular spaces with reconfigurable layouts. The ratio of heavy-duty to lightweight cleanroom space, as well as technical zones, can be tailored to meet the specific needs of each tenant.



Rental rates, lease proposals and terms & conditions are available upon request.



More information:
www.jd7.ch/en/building/rental-spaces



Contact : info@jd7.ch

JD7 South-East Module



SURFACE TYPE	AREA (m²)
Heavy-duty cleanroom	181
Lightweight cleanroom	0
Technical space	145
Airlock & changing rooms	39
TOTAL	365

JD7 North-West Module



SURFACE TYPE	AREA (m²)
Heavy-duty cleanroom	113
Lightweight cleanroom	122
Technical space	93
Airlock & changing rooms	52
TOTAL	380



JAQUET
DROZ 7

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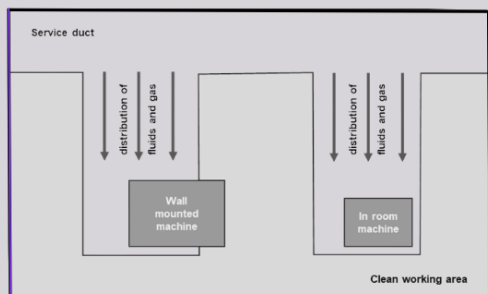
Technical Specifications ISO 5 Cleanroom



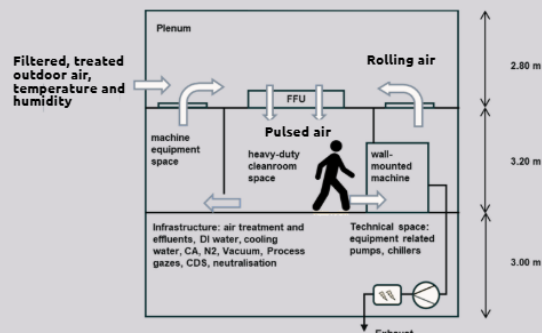
computer-generated image of the future JD7 cleanroom space

JD7's cleanroom infrastructure complies with ISO 14644-1 Class 5 standards (equivalent to Class 100 under the former US FED STD 209E). This classification ensures extremely low airborne particulate levels and highly stable environmental conditions, essential for operations at micro- and nanoscale.

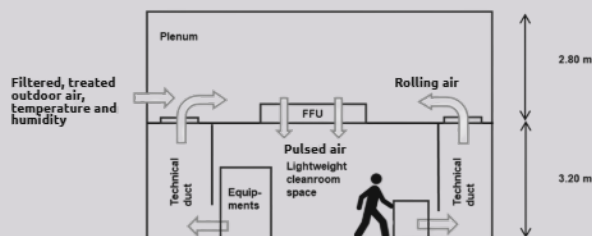
PRINCIPLES



CROSS-SECTION OF A HEAVY-DUTY CLEANROOM



CROSS-SECTION OF A LIGHTWEIGHT CLEANROOM



Key technical features include :

MAXIMUM PARTICLE CONCENTRATIONS

3,520 particles/m³ ($\geq 0.5 \mu\text{m}$)
29 particles/m³ ($\geq 5.0 \mu\text{m}$)

AIR CHANGES PER HOUR

typically 240–600, depending on room layout and process requirements

FILTRATION

High-Efficiency Particulate Air (HEPA) and Ultra-Low Penetration Air (ULPA) filters.

AIRFLOW

unidirectional (laminar flow) with continuous air circulation from ceiling to floor/wall exhausts

PRESSURE REGIME

positive pressure maintained in ISO 5 areas relative to adjacent lower-grade zones to prevent contamination ingress

TEMPERATURE & HUMIDITY CONTROL

precisely regulated (e.g., 20–22 °C, 40–50% RH), critical for photolithography and resist processing

ZONED WORKFLOW DESIGN

clear separation of clean “white” and technical “grey” zones to optimize contamination control

CENTRAL DISTRIBUTION SYSTEM (CDS)

safe, centralized infrastructure for the supply of standard and specialized gases and chemicals, commonly used in micro/nanofabrication and micro-engineering processes

DIRECT ACCESS FOR MAINTENANCE

underfloor technical area and basement access for equipment servicing and process upgrades

ACCESS CONTROL

restricted access to clean areas via secure systems

INGRESS PROTOCOLS

includes airlocks, changing rooms, air showers and pass-through hatches, tailored to tenant specifications

ALL-INCLUSIVE TECHNICAL MANAGEMENT

fully integrated services from day one, including facility operations, environmental monitoring and maintenance

PLUG & PLAY READY

fully operational, scalable, adaptable to your processes and ready to use